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		Application Number	10/576,345		
		Filing Date	April 18, 2006		
		First Named Inventor	MARCHAND, Gilles		
		Art Unit	TBA		
		Examiner Name	TBA		
		Attorney Docket Number	10404.039.00-US		
Sheet	1	of	1		

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
DAG/	AA	6,565,813 B1	05-20-2003	Garyantes	
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Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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DAG/	BA	WO 03/059518 A1	07-24-2003	University College Cork- National University of Ireland, Cork	
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NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			†
DAG/	CA	Azek, F., et al., <i>Hybridization Assay at a Disposal Electrochemical Biosensor for the Attomole Detection of Amplified Human Cytomegalovirus DNA</i> , Analytical Biochemistry, 284, pp. 107-113			
DAG/	CB	Lee, J., et al., <i>Electrowetting and electrowetting-on-dielectric for microscale liquid handling</i> , Elsevier, Dept. of Mechanical Engineering, Northwestern University, pp. 259-268			
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DAG/	CD	Yang, Mengsu, et al., <i>Covalent Immobilization of Oligonucleotides on Modified Glass/Silicon Surfaces for Solid-phase DNA Hybridization and Amplification</i> , The Chemical Society of Japan, 1998, pp. 257-258			
DAG/	CE	Boncheva, M., et al., <i>Design of Oligonucleotide Arrays at Interfaces</i> , American Chemical Society, 1999, pp. 4317-4320			
DAG/	CF	Jansen, H., et al., <i>The black silicon method: a universal method for determining the parameter setting of a fluorene-based reactive ion etcher in deep silicon trench etching with profile control</i> , MESA Research Institute, University of Twente, 1995, pp. 115-120			

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